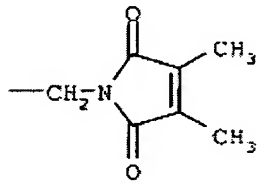
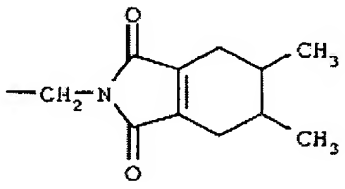
CLAIM AMENDMENTS

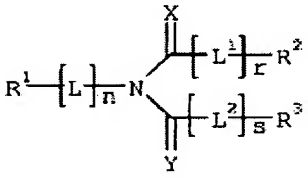
1. (Currently Amended) A polymer comprising a phenolic monomeric unit of which the phenyl group is substituted by a group A, ~~characterised in that the~~ wherein group A comprises an imide or thioimide group[[,]] with the exception that A is not



or

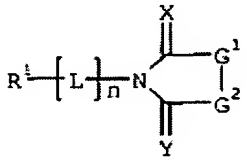


2. (Currently Amended) [[A]] The polymer according to claim 1 wherein the group A has the following formula



wherein X and Y are independently selected from O [[or]] and S,
wherein L, L^1 and L^2 are independently a linking group,
wherein n, r and s are independently 0 or 1,
and wherein one of the groups R^1, R^2 or R^3 represents the phenolic monomeric unit and the other two represent a terminal group.

3. (Currently Amended) [[A]] The polymer according to claim 1 wherein the group A has the following formula



wherein X and Y are independently selected from O [[or]] and S,

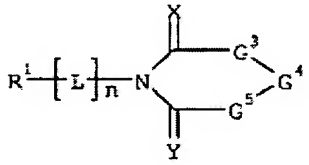
wherein G^1 and G^2 are independently selected from O, S, NR^4 [[or]] and R^5-$[L^3]_t$-C-$[L^4]_u$-R^6, with the limitation that G^1 is not O or S when G^2 is O and that G^1 is not O or S when G^2 is NR^4,

wherein L, L^3 and L^4 are independently a linking group,

wherein n, t and u are independently 0 or 1,

and wherein one of the groups selected from R^1, R^4, R^5 [[or]] and R^6 represents the phenolic monomeric unit and the remaining groups represent a terminal group.

4. (Currently amended) [[A]] The polymer according to claim 1 wherein the group A has the following formula



wherein X and Y are independently selected from O [[or]] and S,

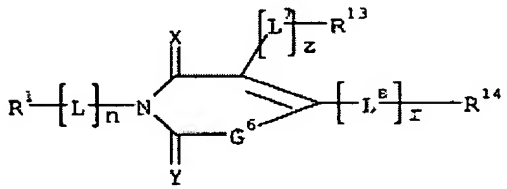
wherein G^3 to G^5 are independently selected from O, S, NR^7 [[or]] and R^8-$[L^5]_v$-C-$[L^6]_w$-R^9 with the limitation that at least one group, selected from G^3 to G^5, is R^8-$[L^5]_v$-C-$[L^6]_w$-R^9 and that two ~~neighbouring~~ neighboring groups, selected from G^3 to G^5, are not represented by O and S, by O and NR^7, by S and NR^7 or by O and O,

wherein L, L^5 and L^6 are independently a linking group,

wherein n, v and w are independently 0 or 1, and

wherein one of the groups selected from R^1, R^7, R^8 [[or]] and R^9 represents the phenolic monomeric unit and the remaining groups represent a terminal group.

5. (Currently Amended) [[A]] The polymer according to claim 1 wherein the group A has the following formula

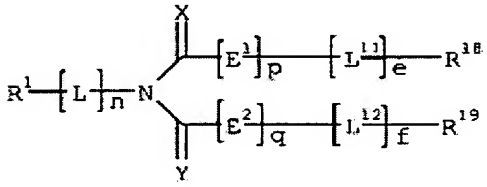


wherein X and Y are independently selected from O [[or]] and S,

wherein G is a group selected from O, S, NR^{10} [[or]] and R^{11}-$[L^9]_x$-C-$[L^{10}]_y$-R^{12},

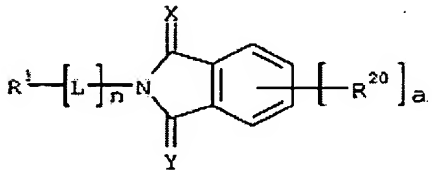
wherein L, L^7, L^8, L^9 and L^{10} are independently a linking group,
wherein n, x, y, z and r are independently 0 or 1, and
wherein one of the groups selected from R^1, R^{10}, R^{11}, R^{12}, R^{13} and R^{14} represents the phenolic monomeric unit and the remaining groups represent a terminal group.

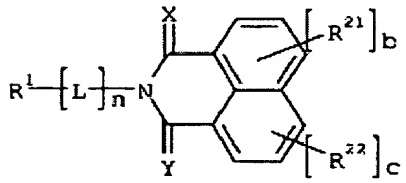
6. (Currently Amended) [[A]] The polymer according to claim 1 wherein the group A has the following formula

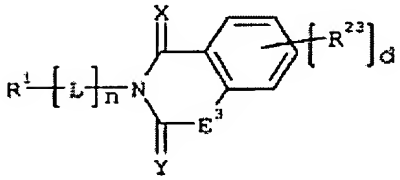


wherein X and Y are independently selected from O [[or]] and S,
wherein E^1 and E^2 are independently selected from O, S, NR^{15} [[or]] and R^{16}-$[L^{13}]_g$-C-$[L^{14}]_h$-R^{17},
wherein n, e, f, g, h, p and q are independently 0 or 1,
wherein e is 0 when E^1 is represented by O, S or NR^{15}, wherein f is 0 when ~~and~~ E^2 is represented by O, S or NR^{15},
wherein L, L^{11}, L^{12}, L^{13} and L^{14} are independently a linking group, and
wherein one of the groups selected from R^1, R^{15}, R^{16}, R^{17}, R^{18} and R^{19} represents the phenolic monomeric unit and the remaining groups represent a terminal group.

7. (Currently Amended) [[A]] The polymer according to claim 1 wherein the group A has one of the following ~~formula~~ formulae







wherein X and Y are independently selected from O [[or]] and S,
wherein each R^1[[,]] and R^{20} to R^{23} ~~are~~ is a terminal group[[,]] independently selected from hydrogen, an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, halogen, $-SO_2-NH-R^{24}$, $-NH-SO_2-R^{27}$, $-CO-NR^{24}-R^{25}$, $-NR^{24}-CO-R^{27}$, $-NR^{24}-CO-NR^{25}-R^{26}$, $-NR^{24}-CS-NR^{25}-R^{26}$, $-NR^{24}-CO-O-R^{25}$, $-O-CO-NR^{24}-R^{25}$, $-O-CO-R^{27}$, $-CO-O-R^{24}$, $-CO-R^{24}$, $-SO_3-R^{24}$, $-O-SO_2-R^{27}$, $-SO_2-R^{24}$, $-SO-R^{27}$, $-P(=O)(-O-R^{24})(-O-R^{25})$, $-O-P(=O)(-O-R^{24})(-O-R^{25})$, $-NR^{24}-R^{25}$, $-O-R^{24}$, $-S-R^{24}$, $-CN$, $-NO_2$, $-N(-CO-R^{24})(-CO-R^{25})$, -N-phthalimidyl, -M-N-phthalimidyl, [[or]] and $-M-R^{24}$,
wherein M represents a divalent linking group containing 1 to 8 carbon atoms,
wherein R^{24} to R^{26} are independently selected from hydrogen [[or]] and an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group,
wherein R^{27} is selected from an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl [[or]] and heteroaralkyl group,
wherein a and d are independently 0, 1, 2, 3 or 4,
wherein b and c are independently 0, 1, 2 or 3,
wherein E^3 is selected from O, S, NR^{28} [[or]] and $R^{29}-[L^{15}]_i-C-[L^{16}]_j-R^{30}$,
wherein L, L^{15} and L^{16} are independently a linking group, wherein n, i and j independently are 0 or 1,
and wherein one of the groups selected from R^1, R^{20}, R^{21}, R^{22}, R^{23}, R^{28}, R^{29} and R^{30} represents the phenolic monomeric unit and the remaining groups represent a terminal group.

8. (Currently Amended) [[A]] The polymer according to ~~any of the preceding claims~~ claim 1, wherein said polymer comprising a phenolic monomeric unit is a novolac, resol or polyvinylphenol.

9. (Currently Amended) A heat-sensitive lithographic printing plate precursor comprising a support having a hydrophilic surface and an oleophilic coating[[,]] provided on the hydrophilic surface, said coating comprising an infrared light absorbing agent and a polymer according to claim 1.

10. (Currently Amended) [[A]] The lithographic printing plate precursor according to claim 9, wherein said coating further comprises a dissolution inhibitor and wherein said precursor is a positive working lithographic printing plate precursor.

11. (Currently Amended) [[A]] The lithographic printing plate precursor according to claim 10, wherein said dissolution inhibitor is selected from the group consisting of

[[-]] an organic compound which comprises at least one aromatic group and a hydrogen bonding site, ~~and/or~~

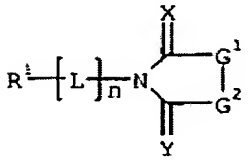
[[-]] a polymer or surfactant comprising siloxane or perfluoroalkyl units, and mixtures thereof.

12. (Canceled)

13. (Currently Amended) [[A]] The heat-sensitive lithographic printing plate precursor according to claim 9, wherein said coating further comprising a latent Brönsted acid and an acid-crosslinkable compound and wherein said precursor is a negative working lithographic printing plate precursor.

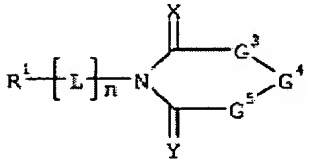
14. (Canceled)

15. (New) The heat-sensitive lithographic printing plate precursor according to claim 9 wherein the group A has the following formula



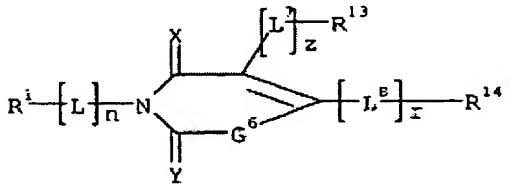
wherein X and Y are independently selected from O and S,
wherein G^1 and G^2 are independently selected from O, S, NR^4 and R^5-$[L^3]_t$-C-$[L^4]_u$-R^6, with the limitation that G^1 is not O or S when G^2 is O and that G^1 is not O or S when G^2 is NR^4,
wherein L, L^3 and L^4 are independently a linking group,
wherein n, t and u are independently 0 or 1,
and wherein one of the groups selected from R^1, R^4, R^5 and R^6 represents the phenolic monomeric unit and the remaining groups represent a terminal group.

16. (New) The heat-sensitive lithographic printing plate precursor according to claim 9 wherein the group A has the following formula



wherein X and Y are independently selected from O and S,
wherein G^3 to G^5 are independently selected from O, S, NR^7 and R^8-$[L^5]_v$-C-$[L^6]_w$-R^9 with the limitation that at least one group, selected from G^3 to G^5, is R^8-$[L^5]_v$-C-$[L^6]_w$-R^9 and that two neighbouring groups, selected from G^3 to G^5, are not represented by O and S, by O and NR^7, by S and NR^7 or by O and O,
wherein L, L^5 and L^6 are independently a linking group, .wherein n, v and w are independently 0 or 1,
and wherein one of the groups selected from R^1, R^7, R^8 and R^9 represents the phenolic monomeric unit and the remaining groups represent a terminal group.

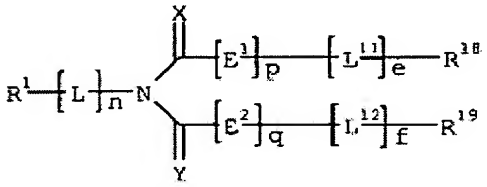
17. (New) The heat-sensitive lithographic printing plate precursor according to claim 9 wherein the group A has the following formula



wherein X and Y are independently selected from O and S,
wherein G is a group selected from O, S, NR^{10} and R^{11}-$[L^9]_x$-C-$[L^{10}]_y$-R^{12},

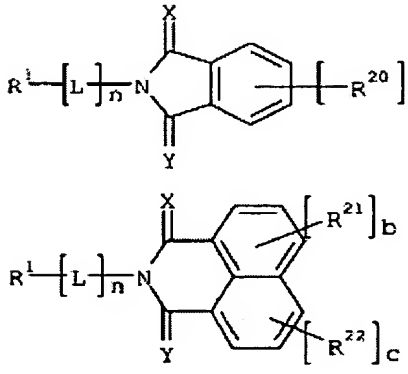
wherein L, L^7, L^8, L^9 and L^{10} are independently a linking group,
wherein n, x, y, z and r are independently 0 or 1,
and wherein one of the groups selected from R^1, R^{10}, R^{11}, R^{12}, R^{13} and R^{14} represents the phenolic monomeric unit and the remaining groups represent a terminal group.

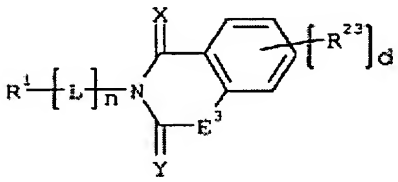
18. (New) The heat-sensitive lithographic printing plate precursor according to claim 9 wherein the group A has the following formula



wherein X and Y are independently selected from O and S,
wherein E^1 and E^2 are independently selected from O, S, NR^{15} and R^{16}-$[L^{13}]_g$-C-$[L^{14}]_h$-R^{17},
wherein n, e, f, g, h, p and q are independently 0 or 1, wherein e is 0 when E^1 is represented by O, S or NR^{15}, wherein f is 0 when E^2 is represented by O, S or NR^{15},
wherein L, L^{11}, L^{12}, L^{13} and L^{14} are independently a linking group,
and wherein one of the groups selected from R^1, R^{15}, R^{16}, R^{17}, R^{18} and R^{19} represents the phenolic monomeric unit and the remaining groups represent a terminal group.

19. (New) The heat-sensitive lithographic printing plate precursor according to claim 9 wherein the group A has one of the following formulae





wherein X and Y are independently selected from O and S,
wherein each R^1 and R^{20} to R^{23} is a terminal group independently selected from hydrogen, an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group, halogen, $-SO_2-NH-R^{24}$, $-NH-SO_2-R^{27}$, $-CO-NR^{24}-R^{25}$, $-NR^{24}-CO-R^{27}$, $-NR^{24}-CO-NR^{25}-R^{26}$, $-NR^{24}-CS-NR^{25}-R^{26}$, $-NR^{24}-CO-O-R^{25}$, $-O-CO-NR^{24}-R^{25}$, $-O-CO-R^{27}$, $-CO-O-R^{24}$, $-CO-R^{24}$, $-SO_3-R^{24}$, $-O-SO_2-R^{27}$, $-SO_2-R^{24}$, $-SO-R^{27}$, $-P(=O)(-O-R^{24})(-O-R^{25})$, $-O-P(=O)(-O-R^{24})(-O-R^{25})$, $-NR^{24}-R^{25}$, $-O-R^{24}$, $-S-R^{24}$, $-CN$, $-NO_2$, $-N(-CO-R^{24})(-CO-R^{25})$, -N-phthalimidyl, -M-N-phthalimidyl, and $-M-R^{24}$,
wherein M represents a divalent linking group containing 1 to 8 carbon atoms,
wherein R^{24} to R^{26} are independently selected from hydrogen and an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl or heteroaralkyl group,
wherein R^{27} is selected from an optionally substituted alkyl, alkenyl, alkynyl, cycloalkyl, heterocyclic, aryl, heteroaryl, aralkyl and heteroaralkyl group,
wherein a and d are independently 0, 1, 2, 3 or 4,
wherein b and c are independently 0, 1, 2 or 3,
wherein E^3 is selected from O, S, NR^{28} or $R^{29}–[L^{15}]_i-C-[L^{16}]_j–R^{30}$, wherein L, L^{15} and L^{16} are independently a linking group,
wherein n, i and j independently are 0 or 1,
and wherein one of the groups selected from R^1, R^{20}, R^{21}, R^{22}, R^{23}, R^{28}, R^{29} and R^{30} represents the phenolic monomeric unit and the remaining groups represent a terminal group.

20. (New) The heat-sensitive lithographic printing plate precursor according to claim 15, wherein said coating further comprises a dissolution inhibitor and wherein said precursor is a positive working lithographic printing plate precursor.

21. (New) The heat-sensitive lithographic printing plate precursor according to claim 16, wherein said coating further comprises a dissolution inhibitor and wherein said precursor is a positive working lithographic printing plate precursor.

22. (New) The heat-sensitive lithographic printing plate precursor according to claim 17, wherein said coating further comprises a dissolution inhibitor and wherein said precursor is a positive working lithographic printing plate precursor.

23. (New) The heat-sensitive lithographic printing plate precursor according to claim 18, wherein said coating further comprises a dissolution inhibitor and wherein said precursor is a positive working lithographic printing plate precursor.

24. (New) The heat-sensitive lithographic printing plate precursor according to claim 19, wherein said coating further comprises a dissolution inhibitor and wherein said precursor is a positive working lithographic printing plate precursor.

25. (New) The heat-sensitive lithographic printing plate precursor according to claim 15, wherein said coating further comprising a latent Brönsted acid and an acid-crosslinkable compound and wherein said precursor is a negative working lithographic printing plate precursor.

26. (New) The heat-sensitive lithographic printing plate precursor according to claim 16, wherein said coating further comprising a latent Brönsted acid and an acid-crosslinkable compound and wherein said precursor is a negative working lithographic printing plate precursor.

27. (New) The heat-sensitive lithographic printing plate precursor according to claim 17, wherein said coating further comprising a latent Brönsted acid and an acid-crosslinkable compound and wherein said precursor is a negative working lithographic printing plate precursor.

28. (New) The heat-sensitive lithographic printing plate precursor according to claim 18, wherein said coating further comprising a latent Brönsted acid and an

acid-crosslinkable compound and wherein said precursor is a negative working lithographic printing plate precursor.

29. (New) The heat-sensitive lithographic printing plate precursor according to claim 19, wherein said coating further comprising a latent Brönsted acid and an acid-crosslinkable compound and wherein said precursor is a negative working lithographic printing plate precursor.

30. (New) The polymer according to claim 2, wherein said polymer comprising a phenolic monomeric unit is a novolac, resol or polyvinylphenol.

31. (New) The polymer according to claim 3, wherein said polymer comprising a phenolic monomeric unit is a novolac, resol or polyvinylphenol.

32. (New) The polymer according to claim 4, wherein said polymer comprising a phenolic monomeric unit is a novolac, resol or polyvinylphenol.

33. (New) The polymer according to claim 5, wherein said polymer comprising a phenolic monomeric unit is a novolac, resol or polyvinylphenol.

34. (New) The polymer according to claim 6, wherein said polymer comprising a phenolic monomeric unit is a novolac, resol or polyvinylphenol.

35. (New) The polymer according to claim 7, wherein said polymer comprising a phenolic monomeric unit is a novolac, resol or polyvinylphenol.

36. (New) A method for increasing the chemical resistance of a coating of a positive working heat-sensitive lithographic printing plate precursor against printing liquids and press chemicals, the method comprising providing a coating comprising:

a polymer according to claim 1,

an infrared absorbing agent, and

a dissolution inhibitor.

37. (New) A method for increasing the chemical resistance of a coating of a negative working heat-sensitive lithographic printing plate precursor against printing liquids and press chemicals, the method comprising providing a coating comprising:

a polymer according to claim 1,

a latent Brönsted acid, and

an acid-crosslinkable compound.